



Serial No. 09/715,041
SEC.741
Response dated February 13, 2004

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent application of : **FEB 20 2004**
Sang-Jun CHOI et al. : Group Art Unit 1752
Serial No. 09/715,041 : Examiner Yvette C. Thornton
Filed November 20, 2000 :

PHOTORESISTIVE POLYMER HAVING CYCLIC BACKBONE AND RESIST COMPOSITION
CONTAINING THE SAME

**REQUEST FOR RECONSIDERATION
AFTER FINAL**

U.S. Patent and Trademark Office
2011 South Clark Place
Customer Window, **Mail Stop AF**
Crystal Plaza Two, Lobby, Room 1B03
Arlington, VA 22202

Sir:

This is in response to the final Office action dated September 16, 2003.

Claims 1, 2, 5, 6 and 9-18 remain pending in the application.

35 USC 112, first paragraph

The Examiner has rejected the claims on the grounds that the specification fails to support the relationship " $m + n = 1$ ".

However, Applicants respectfully point out that " $m + n = 1$ " is simply another way of saying that the polymer contains no other monomers. The specification

contains numerous examples of two-monomer polymers, and such two-monomer polymers are clearly enabled by the specification.

Accordingly, reconsideration of the rejection under 35 USC 112, first paragraph, is requested.

35 USC 102/103

Claims 1, 2, 5, 6 and 9-18 were rejected under 35 USC 102 and 103 as being unpatentable over Kinsho et al. Applicants respectfully traverse this rejection.

The Examiner contends that the “consisting essentially” language of the claims is insufficient to preclude additional monomers such as those disclosed by Kinsho et al. However, as noted previously, the now pending claims include the limitation of “ $m + n = 1$ ”, which means that no other monomers are present in the claimed polymer. Thus, the pending claims can not be anticipated by Kinsho et al.

The Examiner further contends that it would be obvious to eliminate selected monomers of Kinsho et al. to arrive at the presently claimed invention. Applicants respectfully disagree.

First, there is nothing in Kinsho et al. or the record as a whole which might motivate one of ordinary skill to eliminate monomers contained in the specific terpolymers of Kinsho et al.

Second, the presently claimed invention is directed to a random copolymer of maleic anhydride and (meth)acrylate derivative having acid labile group, which is characterized by a more simple structure and better properties than the conventional terpolymer or tetrapolymer. The copolymer the claimed copolymer provides enhanced contrast and has high dry etch resistance because it has increased monomeric ratios of a polymerization unit of acrylate having an acid labile group and a polymerization unit of acrylate having a bulky alkyl group than a general terpolymer or tetrapolymer.

For at least the reasons stated above, Applicants respectfully contend that claims 1, 2, 5, 6 and 9-18 are neither anticipated by nor obvious in view of the cited Kinsho et al. reference.

Conclusion

No other issues remaining, reconsideration and favorable action upon the claims 1, 2, 5, 6 and 9-18 now pending in the application are requested.

Respectfully submitted,

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